

Form PTO-1449 (modified)		Atty. Docket No. 102-0102US	Serial No. unk
List of Patents and Publications for Applicant's INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)		Inventor/Applicant: Neal R. Rueger / Micron Technology, Inc.	
		Title: <b>IMPROVED INDUCTIVELY COUPLED PLASMA CHAMBER ATTACHABLE TO A PROCESSING CHAMBER FOR ANALYSIS OF PROCESS GASES</b>	
		Filing Date: herewith	Group: unk

### U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
	A1						

### Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No
	B1						

### Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
✓	C1	Bladimiro Ruiz, Jr. & Herbert E. Litvak, "Investigation of Silicon Trench Etch Chemistry Using a Downstream Chemical Monitor," 4th AVS Int'l Conference on Microelectronics and Interfaces (2003)
✓	C2	Freddy Gaboriau et al., "Langmuir Probe Measurements in an Inductively Coupled Plasma: . . .," J. Vac. Sci. Technol., Vol. A20(3), pp. 919-27 (May/Jun 2002);
✓	C3	M.V. Malyshev et al., "Diagnostic Studies of Aluminum Etching in an Inductively Coupled Plasma System: . . .," J. Vac. Sci. Technol., Vol. A18(3), pp. 849-59 (May/Jun 2000)
✓	C4	D.M. Manos et al., "Characterization of Laboratory Plasmas With Probes," J. Vac. Sci. Technol., Vol. A3(3), pp. 1059-66 (May/Jun 1985)
✓	C5	S.M. Rossnagel et al., "Langmuir Probe Characterization of Magnetron Operation," J. Vac. Sci. Technol., Vol. A4(3), pp. 1822-25 (May/Jun 1986)
✓	C6	V. Kaepplin et al., "Ion Energy Distribution Functions and Langmuir Probe Measurements in Low Pressure Argon Discharges," J. Vac. Sci. Technol., Vol. A20(2), pp. 526-29 (Mar/Apr 2002)
✓	C7	Terry A. Miller, "Optical Emission and Laser-Induced Fluorescence Diagnostics," J. Vac. Sci. Technol., Vol. A4(3), pp. 1768-72 (May/Jun 1986)

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Exam. Init.	Ref. Des.	Citation
✓	C8	V.M. Donnelly, "A Simple Optical Emission Method for Measuring Percent Dissociations of Feed Gases in Plasmas: . . .," J. Vac. Sci. Technol., Vol. A14(3), pp. 1076-87 (May/Jun 1996)
✓	C9	A.D. Kuypers et al., "Emission Spectroscopy and Actinometry in a Magnetized Low Pressure Radio Frequency Discharge," J. Vac. Sci. Technol., Vol. A8(5), pp. 3736-45 (Sep/Oct 1990)
✓	C10	Zhimin Wan et al., "Electron Cyclotron Resonance Plasma Reactor for SiO <sub>2</sub> Etching: . . .," J. Vac. Sci. Technol., Vol. A13(4), pp. 2035-43 (Jul/Aug 1995)
	C11	

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